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10518060, J. GALL: 1796

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Not for submission under 37 CFR 1.99)

Application Number		10518060			
Filing Date		2005-06-09			
First Named Inventor	Lutz L	ehmann			
Art Unit		1712			
Examiner Name	Kual	iang Peng	Robert	Loewe	
Attorney Docket Numb	er	H26787.685	96 US - 4780		

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			Attorney Do	cket Numl	er	H26787.68596	S US - 4780	
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			Attorney Docket Num	ber	H26787.68596 US - 478	0
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